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PATENT AND TRADEMARK OFFICEATTY DOCKET NO.
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NEW APPLICATION

LIST OF REFERENCES CITED BY APPLICANT

APPLICANT

Shuzhong WANG et al.

FILING DATE

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U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA	6,080,886	06-27-00	LAL et al.			
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						
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	AN						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO	
	AO	1-199922	08-11-89	JAPAN w/Attached English Abstract		X
	AP	6-135869	05-17-94	JAPAN w/Attached English Abstract		X
	AQ	WO 96/03357	02-08-96	WIPO		
	AR					
	AS					
	AT					
	AU					
	AV					

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)

	AW	Frederique Tellier et al., "Introduction Stereoselective Du Groupement Trifluoromethyl Dans Des Systems Insatures," <i>Tetrahedron Letters</i> , Vol. 32, No. 42, pp. 5963-5964, 1991.
	AX	A. J. Downs, "A Cryoscopic Investigation of the Interaction of Bis(Trifluoromethyl) Mercury with Halide Ions", <i>J. Inorg. Nucl. Chem.</i> , 1964, Vol. 26, pp. 41-46.
	AY	
	AZ	

Examiner

Date Considered

*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.